Attorney's Docket No.: 07977 7.10005 / US2941D1D1D1

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

#100 Amot

M. Beunson

blicant : Kusumoto, et al.

Art Unit : Examiner :

2814

Theresa T. Doan

Filed

: August 28, 2001

Title :

August 28, 2001

: METHOD FOR PRODUCING INSULATED GATE THIN FILM

SEMICONDUCTOR DEVICE

Commissioner for Patents Washington, D.C. 20231

Serial No.: 09/941,367

RESPONSE TO RESTRICTION REQUIREMENT AND AMENDMENT

Responsive to the action mailed November 26, 2002, applicants elect the invention of Group I drawn to the embodiment of claims 1, 2, 9-10 and 17-20. The election is made without traverse.

Further, applicants wish to amend the application as follows:

In the claims:

Please amend claims 17-20 as follows:

-- 17. A method according to any one of claims 1, 2, 9 and

10, wherein said semiconductor layer comprises amorphous

silicon.

JAN -3 ZOO

CERTIFICATE OF MAILING BY FIRST CLASS MAI

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail with sufficient postage on the date indicated below and is addressed to the Commissioner for Patents, Washington, D.C. 20231.

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